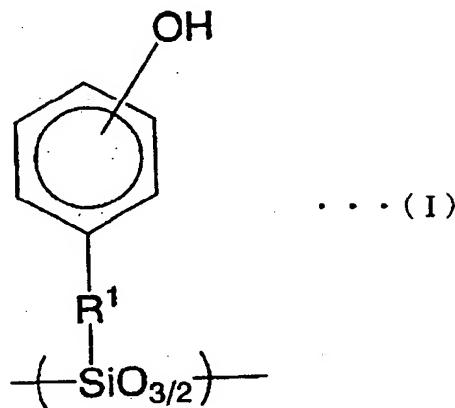


ABSTRACT

The negative resist composition of the present invention comprises a silsesquioxane resin (A) comprising a constituent unit (a1) represented by the following general formula (I) and a constituent unit (a2) represented by the following general formula (II), an acid generator component (B) which generates an acid upon exposure, and a crosslinking agent component (C):

[Chemical Formula 1]



wherein R¹ represents a linear or branched alkylene group having 1 to 5 carbon atoms, and

[Chemical Formula 2]

